

**AMENDMENTS TO THE CLAIMS:**

*This listing of claims will replace all prior versions, and listings, of claims in the application:*

1-5. (Canceled)

6. (Previously presented) A method of making a solar cell, the method comprising:  
forming a layer comprising amorphous silicon,  
wherein the layer comprising amorphous silicon is formed by a plasma CVD  
method comprising employing plasma discharge caused by application of a pulse-  
modulated high frequency voltage having a pulse ON time of not longer than 10  $\mu$  sec  
and a duty ratio of a pulse-modulated high frequency voltage used in said forming is not  
higher than 20% to improve a photo-electric conversion efficiency of the solar cell, and  
in order to form the layer comprising amorphous silicon, applying first and second  
high frequency voltages between a first pair of electrodes and between a second pair of  
electrodes, respectively, to cause plasma discharge, the first and second high frequency  
voltages being modulated in accordance with first and second pulse waves, respectively,  
wherein ON periods of the first and second pulse waves are controlled so as not to  
overlap or coincide with each other, and wherein ON periods of the first and second pulse  
waves are shorter than corresponding OFF periods.

7. (Canceled)

8. (Previously presented) The method of claim 6, wherein a duty ratio of the pulse-modulated high frequency voltage is not higher than 50%.

9. (Canceled)

10. (Previously presented) The method of claim 6, wherein the ON periods of the first and second waves are spaced apart to provide OFF periods in between.